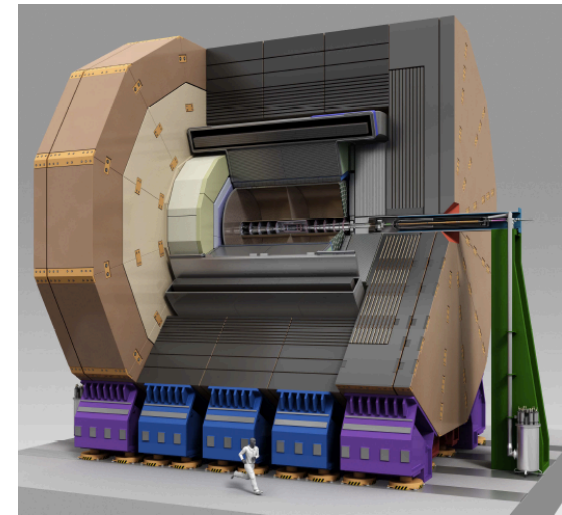
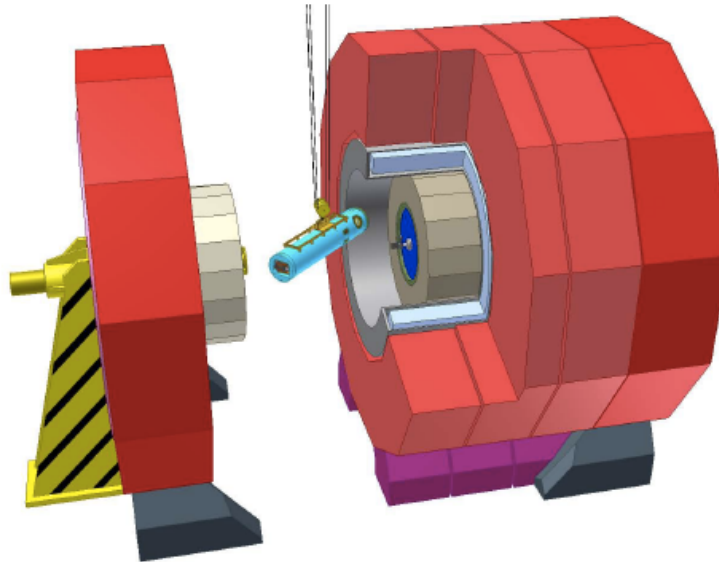
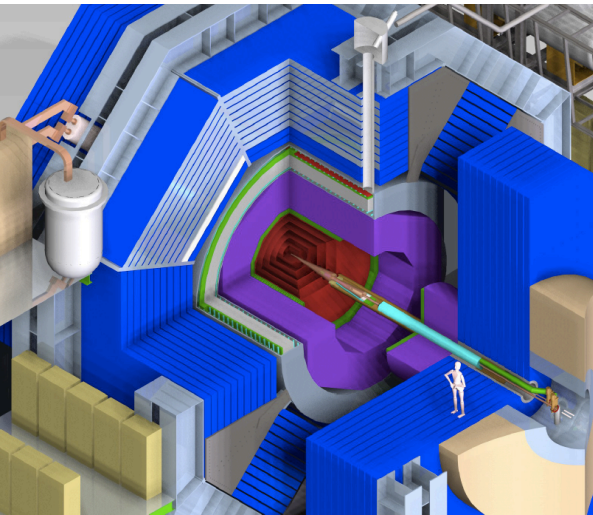


Recent advances in Linear Collider detector R&D



Lucie Linssen, CERN
with input from many LC colleagues



Recent advances in LC detector R&D



ilcILD.org



AIDA

Disclaimer:

Impossible to pay justice to the ongoing detector R&D in 25 minutes !
This talk concentrates on **recent 2011-2012** advances in detector technology
Collection of snapshots

- Linear collider detector requirements
- Vertex detectors
- Tracking
- Calorimetry (electromagnetic)
- Calorimetry (hadronic)
- Forward calorimetry
- Detector engineering
- Coil
- Summary and outlook

High-precision physics calls for:

- Jet energy resolution of $\sigma_E/E \lesssim 3.5\%$ for jet energies from 100 GeV to 1 TeV ($\lesssim 5\%$ at 50 GeV);
- Track momentum resolution of $\sigma_{p_T}/p_T^2 \lesssim 2 \cdot 10^{-5} \text{ GeV}^{-1}$;
- Impact parameter resolution with $a \lesssim 5 \mu\text{m}$ and $b \lesssim 15 \mu\text{m GeV}$, where the resolution is expressed as:

$$\sigma_{d_0}^2 = a^2 + \frac{b^2}{p^2 \sin^3 \theta},$$

- Lepton identification efficiency better than 95% over the full range of energies;
- Detector coverage for electrons down to very low angles.

Additional requirement, due to experimental conditions:

- Manageable occupancies in the presence of beam-induced background
- Radiation hardness for forward calorimetry

Moreover, timing capabilities required for CLIC:

- All tracking detectors with ~ 10 ns time-stamping capability
- Time precision on calorimeter hits of ~ 1 ns

These requirements lead to the following challenges:

Vertex and tracker

- Very high granularity
- Dense integration of functionalities
- Super-light materials
- Low-power design + power pulsing
- Air cooling

ultra – light

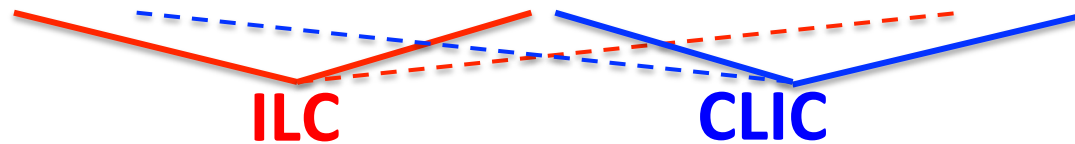
Calorimetry

- Fine segmentation in R, phi, Z
- Ultra – compact active layers
- Pushing integration to limits
- Power pulsing

**ultra – heavy
and compact**

Categories of candidate technologies

	Monolytic CMOS	(3D) integrated	Hybrid pixel
Examples	DEPFET, FPCCD, MAPS, HV-CMOS	SOI MIT-LL, Tezzaron, Ziptronix	CLICpix (TimePix3, Smallpix)
Technology	Specialised HEP processes, r/o and sensors integrated	Customized niche industry Processes with focus on Interconnectivity	Industry standard ASIC processes; HEP-specific high-resistivity sensors
Depletion layer	Partial	Partial or full	Full => large fast signals
Granularity	Down to 5 μm pixel size	Down to 5 μm pixel size	25 μm pixel size
Thickness	$\sim 50 \mu\text{m}$ total thickness achievable	$\sim 50 \mu\text{m}$ total thickness achievable	$\sim 50 \mu\text{m}$ sensor + $\sim 50 \mu\text{m}$ r/o



Categories of candidate technologies

	Monolytic CMOS	(3D) integrated	Hybrid pixel
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Technology	Specialised HEP processes, r/o and	Customized niche industry	Industry standard ASIC processes;

Smaller pixels



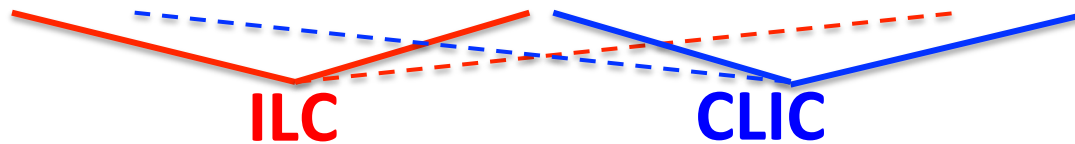
Thinner detectors



High level of pixel functionality



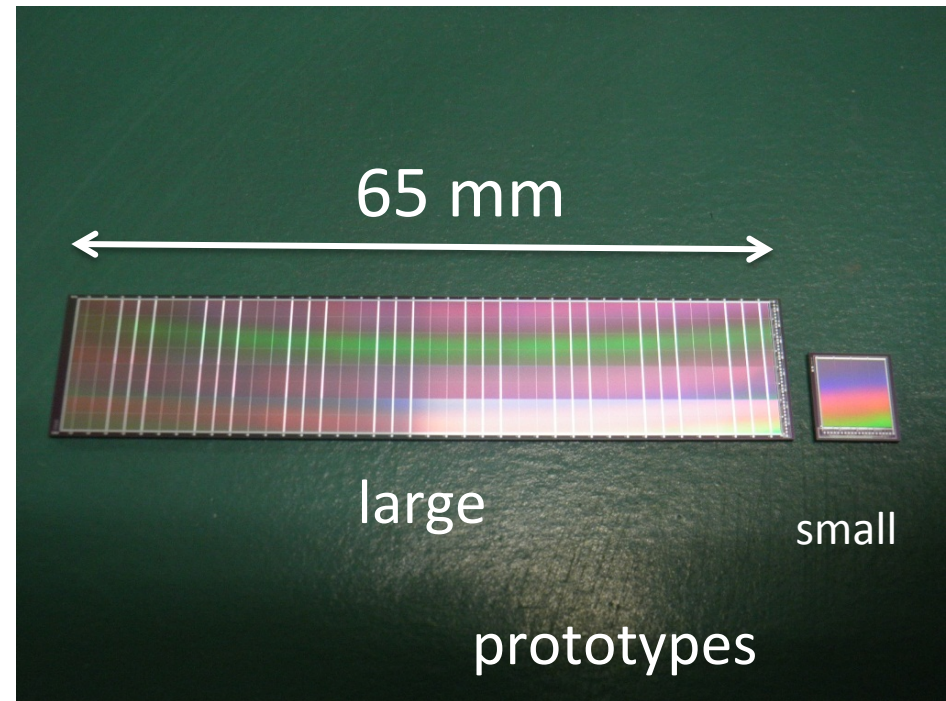
Fast time-stamping



ILC

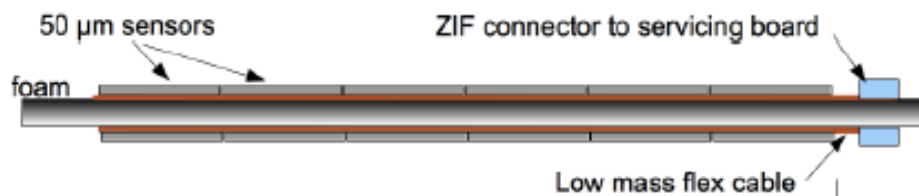
CLIC

- Design of **FPCCD** vertex detector
 - **~5 μm pixel for inner 2 layers** \rightarrow sub - μm point resolution expected
 - **~10 μm pixel for outer 4 layers**
 - Acceptable pixel occupancy even with signal accumulation over 1 bunch-train
 - Relatively slow readout speed of ~10M pixels/s
- **Recent highlight of sensor R&D**
 - **Small (6 mm \times 6 mm) prototype**
 - 4ch (output nodes)/chip
 - All 6 μm pixels
 - It works!
 - **Large (65 mm \times 13.4 mm) prototype**
 - Almost real size prototype for inner layers
 - 8ch/chip
 - 12 μm (2ch), 8 μm (2ch), and 6 μm (4ch) pixels
 - To be tested



Monolithic sensor, CMOS process with high-resistivity epitaxial layer

- Electronics integrated in pixel
- Correlated-Double Sampling (CDS) in pixel
- Rolling shutter read-out (coarse timing)
- Analog or digital readout possible

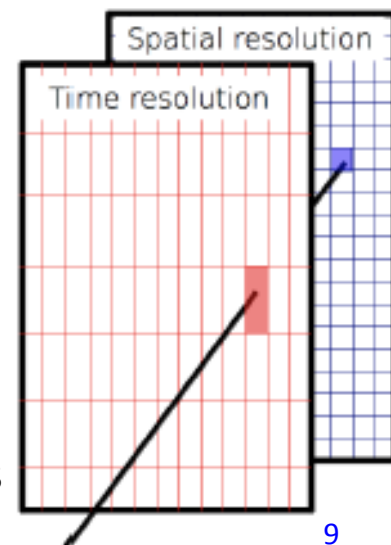
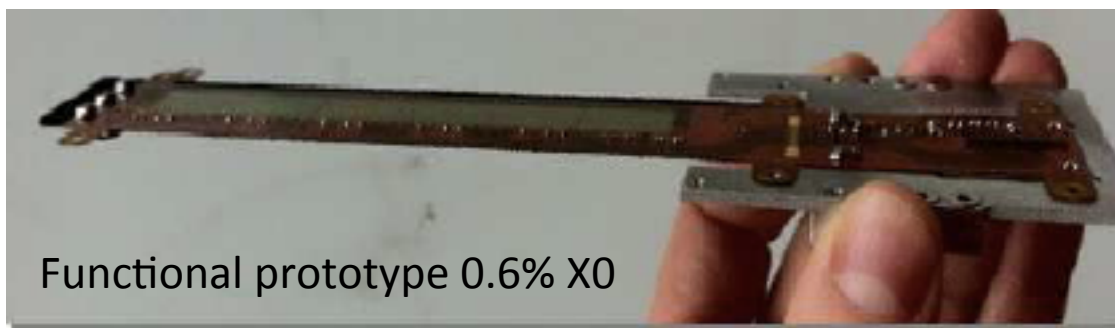
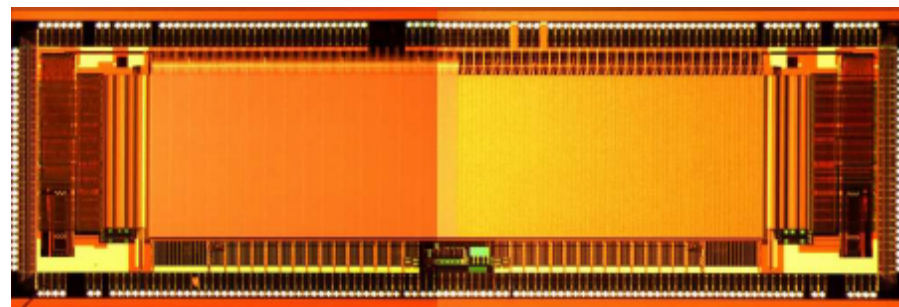


2 types of sensors for inner and outer layers

MIMOSA-30 : Dual sided readout out

- 1 side for spatial resolution (16x16 μm pixel),
- 1 side for timing ($\sim 10\mu\text{s}$, 16x64 μm pixel)

MIMOSA-31 : Larger pixel for reduced power consumption (35x35 μm)



Further R&D: increased epitaxial layer, 180 nm CMOS, thinner assemblies

3D - interconnect and active edge sensor development

Synergy with other projects (LHC upgrades)

3D multi-tier wafer assembly

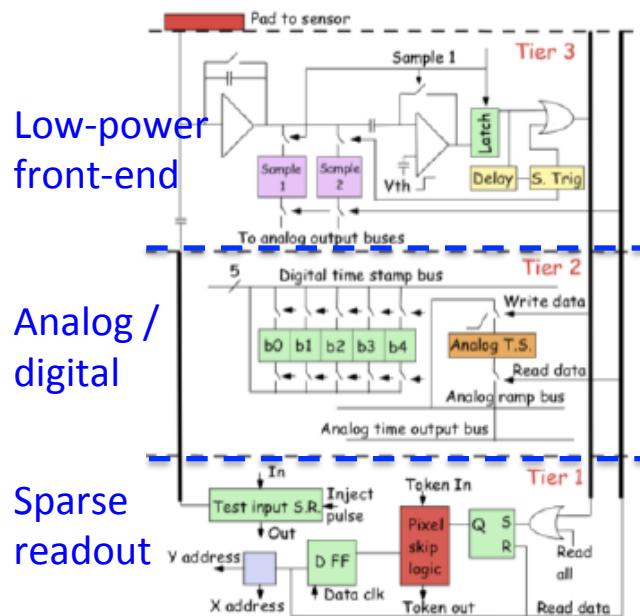
For high-density functionality

Allows for optimal combination of processes: ASIC+sensor

Successful full VIP2b-3D 0.13 nm CMOS run at Tezzaron

Earlier 2D tests => good functionality

3D testing is underway



Chronopixel R&D

Monolithic-CMOS, with time-slicing $\sim 10 \mu\text{s}$

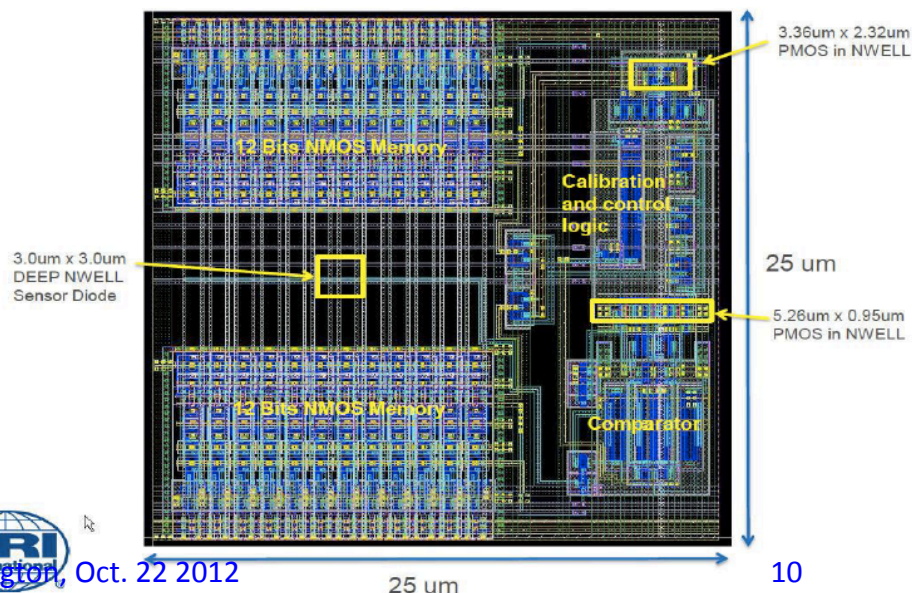
Ultimate design will require 45 nm technology

2nd prototype:

- Recently fabricated in 90 nm technology
- Pixel size $25 \times 25 \mu\text{m}^2$
- Implementing lessons from 1st prototype

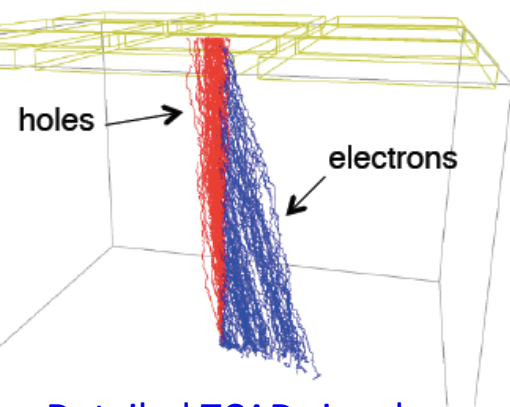
Received from foundry, June 2102.

Looking forward to results of ongoing tests



Hybrid approach:

- Thin ($\sim 50 \mu\text{m}$) sensors (e.g. Micron, CNM, VTT)
- Thinned High density ASIC in very-deep-sub-micron:
 - TimePix3, Smallpix \leq R&D steps
 - CLICpix
- Low-mass interconnect
 - Micro-bump-bonding
 - Through-Silicon-Vias (R&D with CEA-Leti)
 - Chip-stitching
- Power pulsing and air cooling foreseen



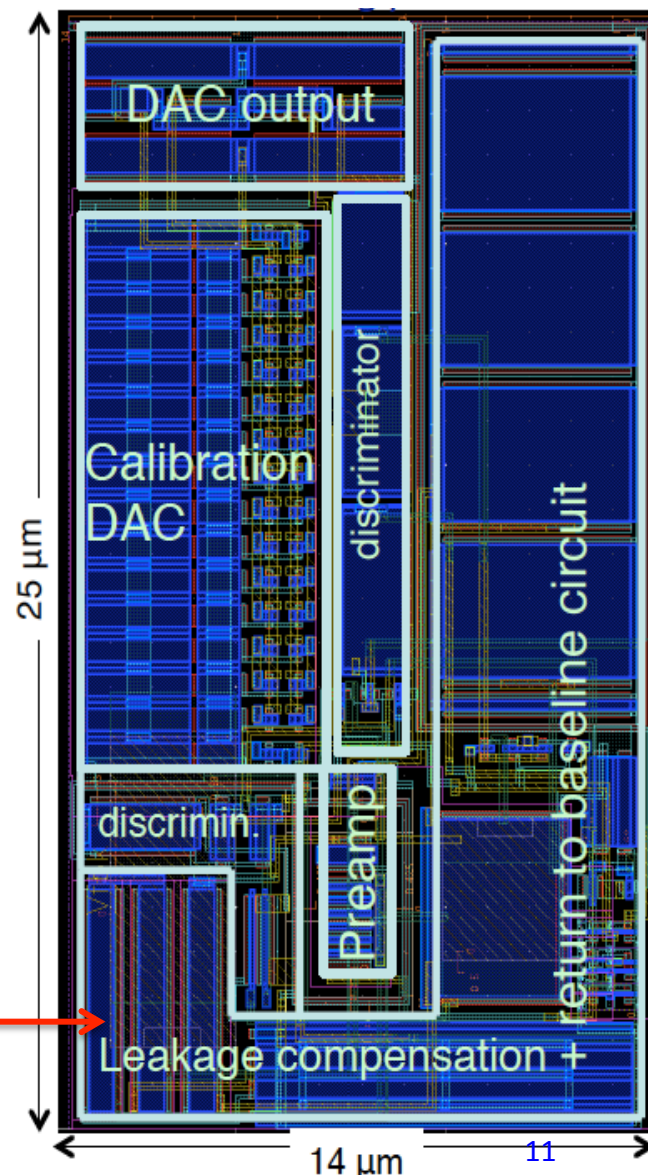
Detailed TCAD signal formation simulation

CLICpix

- 65 nm technology
- $25 \times 25 \mu\text{m}^2$ pixels
- 4-bit TOA and TOT information
 - 10 nsec time-slicing
- Power 2 W/cm^2 (continuous)
- With sequential power pulsing
 - 50 mW/cm^2

64x64 pixel demonstrator
Submission November 2012

Analog part of a CLICpix pixel



Vertex power pulsing design + first lab tests:

- With vertex analog powering in mind: ~ 2 A at 1.2 V for ~ 15 μ s
- **Low-mass !**

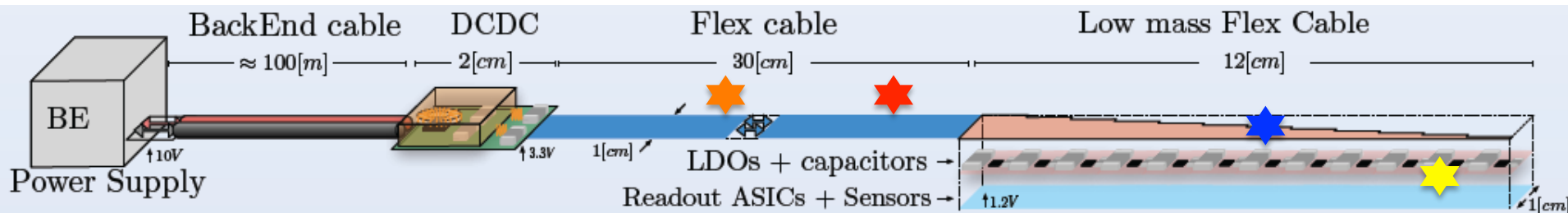


Figure: Half ladder proposed powering scheme

Emulation of: DC-DC converter + flex cable + (LDO/capacitors) + Pixel module

Equivalent 0.145% X0/layer in vertex region

20 mV Voltage ripple achieved

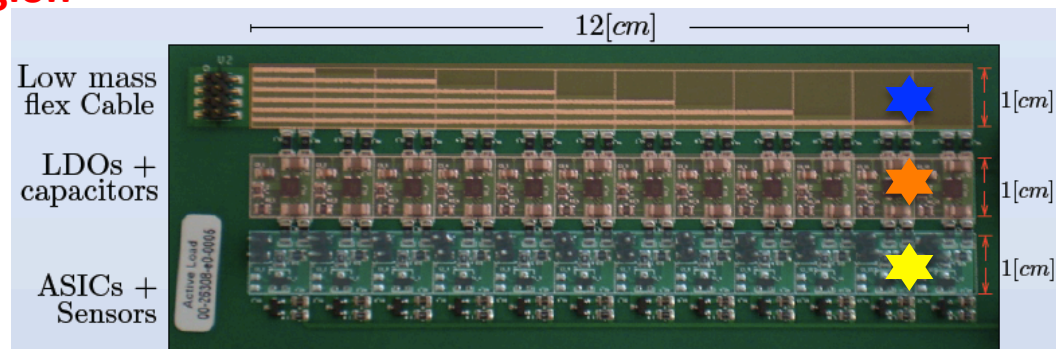
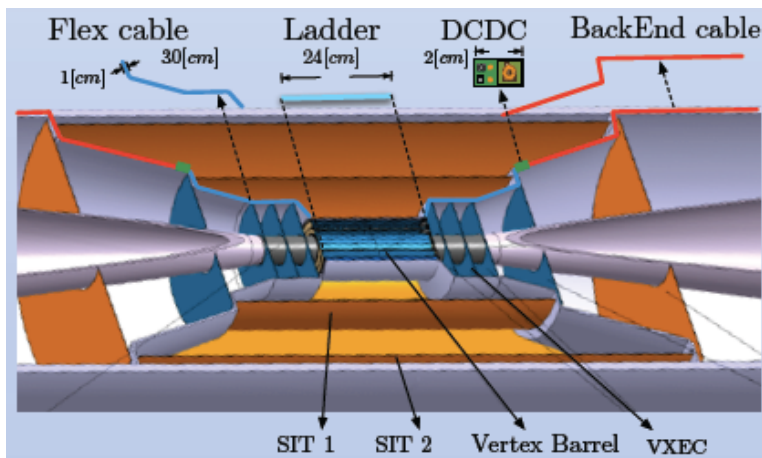
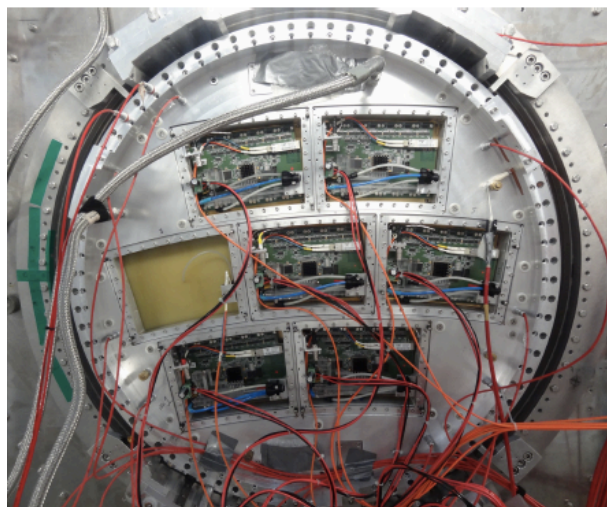
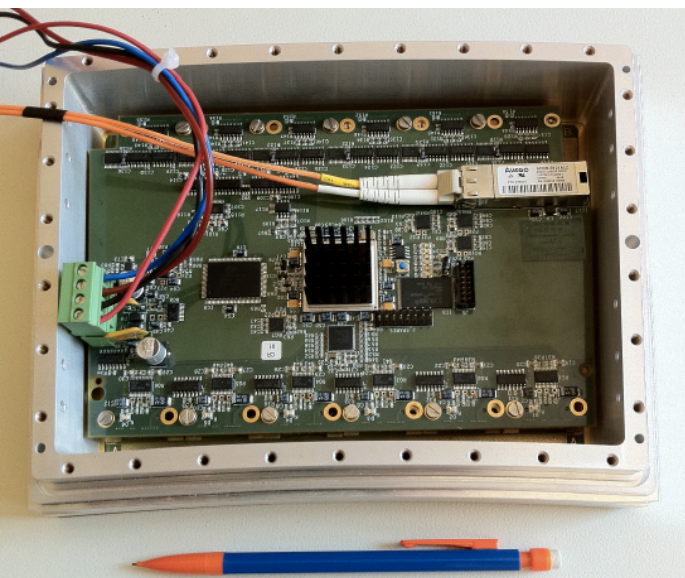


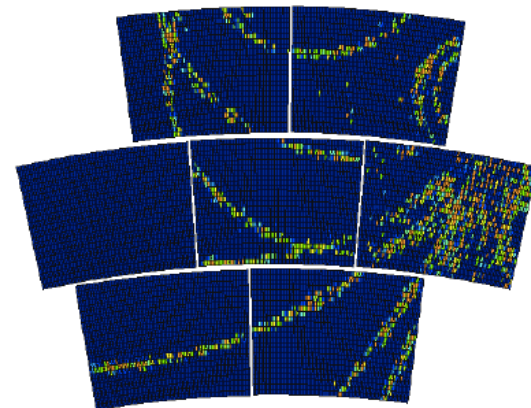
Figure: PCB that emulates the readout ASICs power consumption. It integrates the low mass flex cable, the array of LDOs and capacitors, and their interconnections.



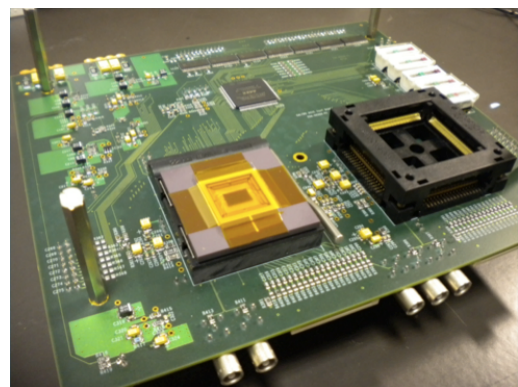
Figure: 30 cm long Flex cable



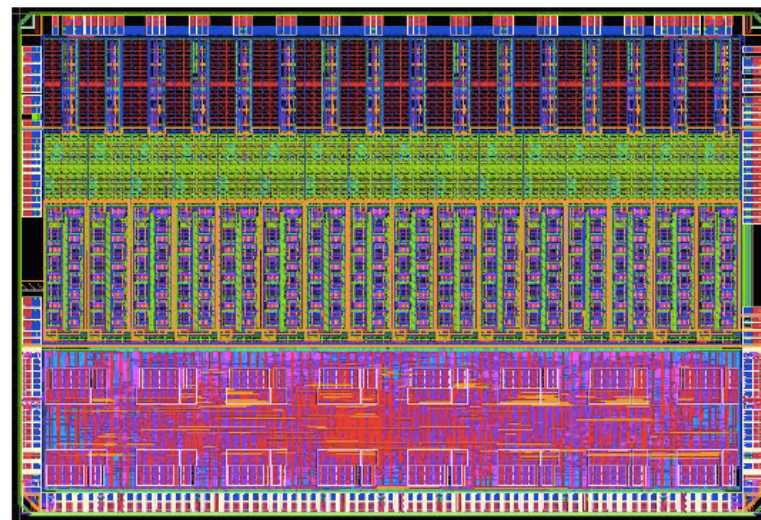
Cosmic muon shower



Six **highly integrated Micromegas** modules with resistive anode

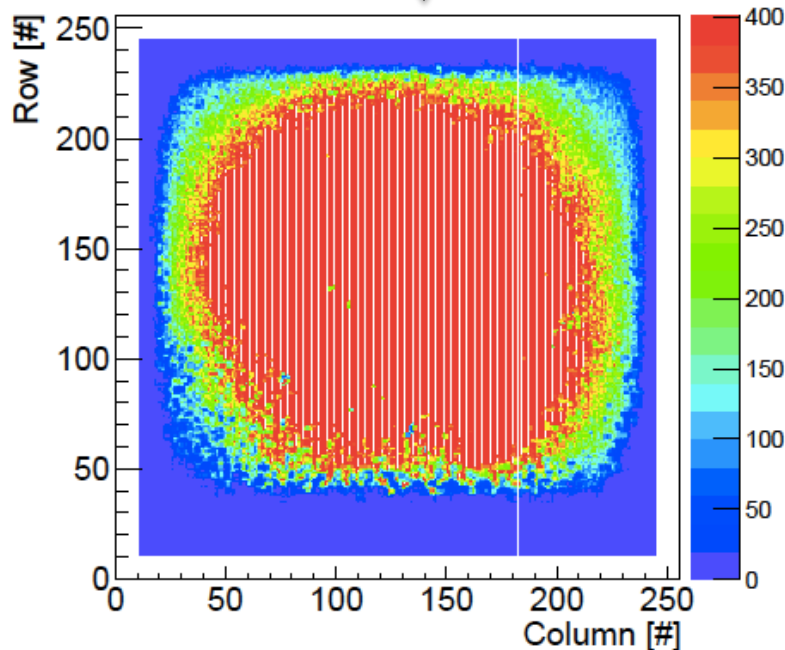


S-Altro16 (130 nm)
Highly integrated analog
+digital TPC readout chip
=> Fully tested and available

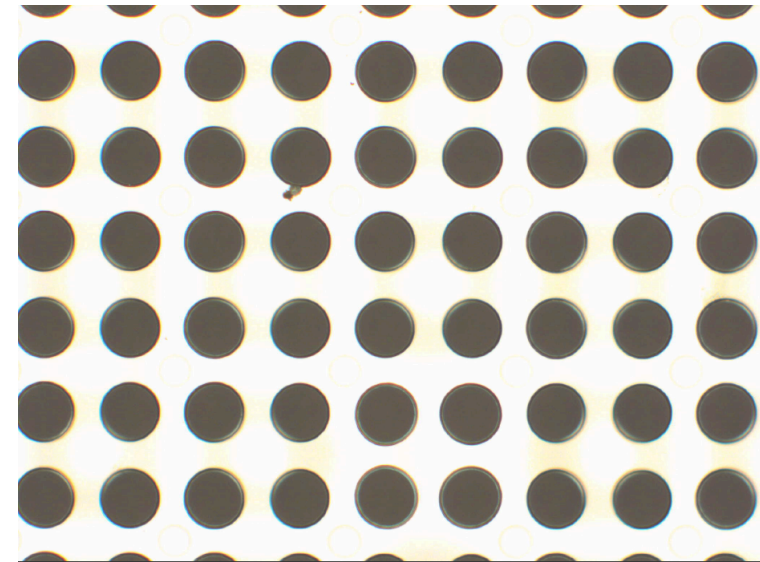


Power pulsing at 50 Hz => factor 18 gain in power

- **New Ingrid production** of one wafer (at IZM)
- Major improvement in the protection layer (Si-Nitride)
- All tested Ingrids have survived more than 5 weeks
 - even with high gain (i.e. more frequent sparking)
- Good signal uniformity, only very few closed holes



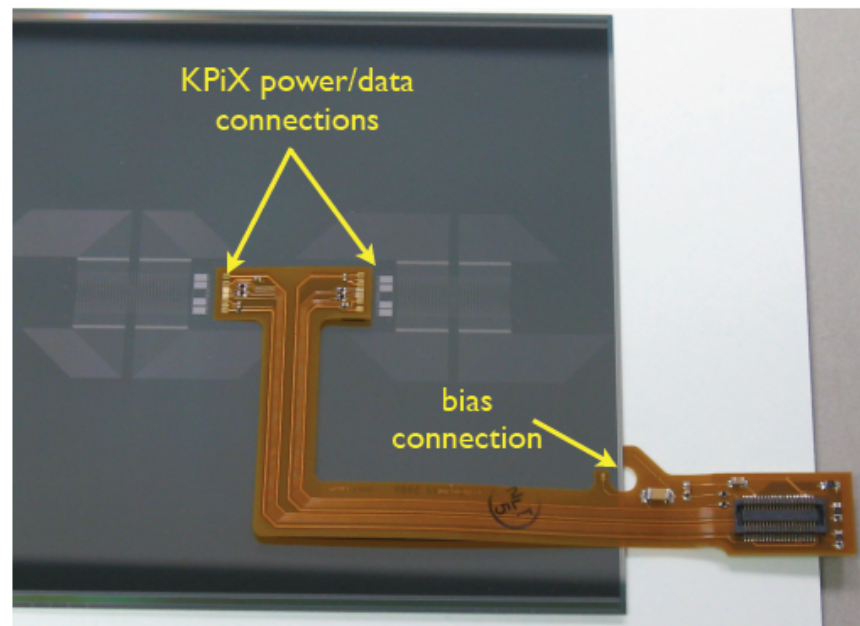
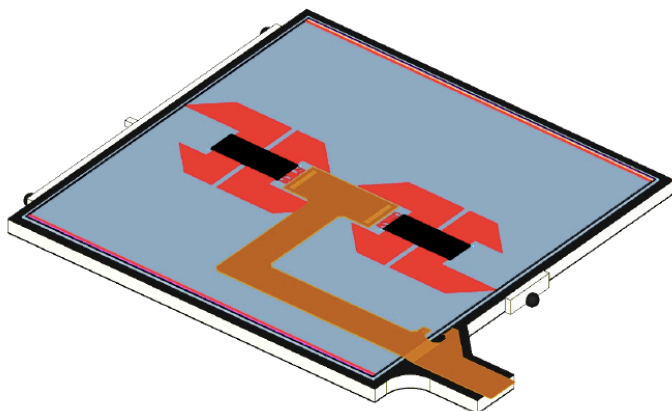
Source illumination near centre of the chip



55 μm

Several other TPC R&D not covered here:
Double / triple GEM studies, Octopus etc

SiD tracker module



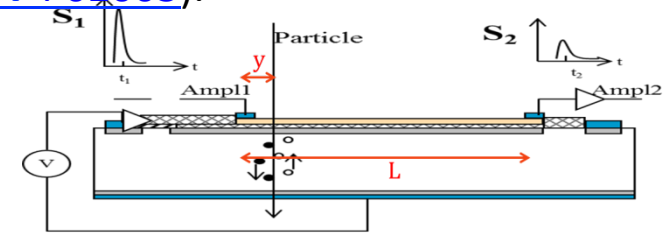
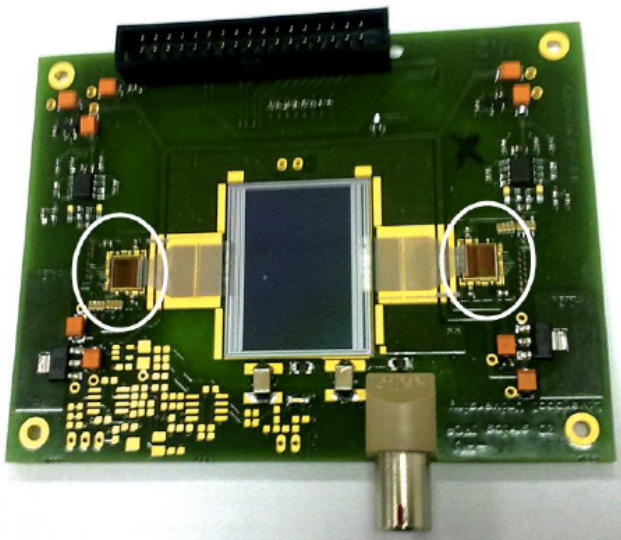
- 1024-channel KPIX chip is produced and tested
- Sensor with double metal-layer routing is available
- Kapton pig-tail available (bonding compatibility)

Pending possibilities to fully bond chip-on-sensor:
tests are ongoing, combining KPIX chip and new pigtail connection.

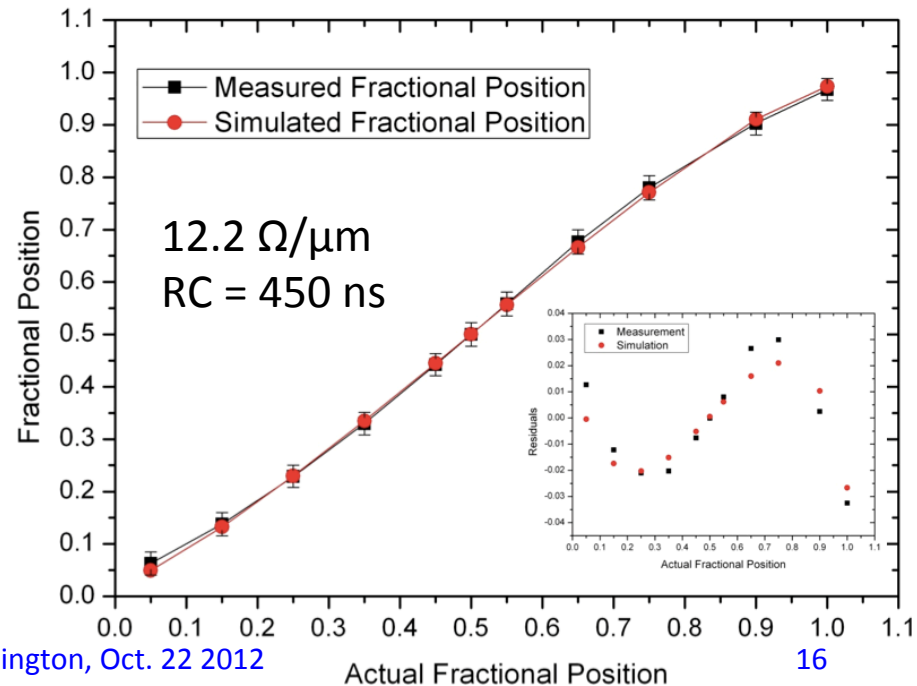
Charge division for 2nd coordinate in microstrip silicon sensors

- Aim: determine the coordinate along the strip. Implemented with slightly resistive electrodes (doped polysilicon) => interesting for low-occupancy tracker regions
- **Position accuracy of a few percent of the microstrip length achieved**
- on the first prototypes (POLYSTRIPS sensors, [2012 JINST 7 P02005](#)).

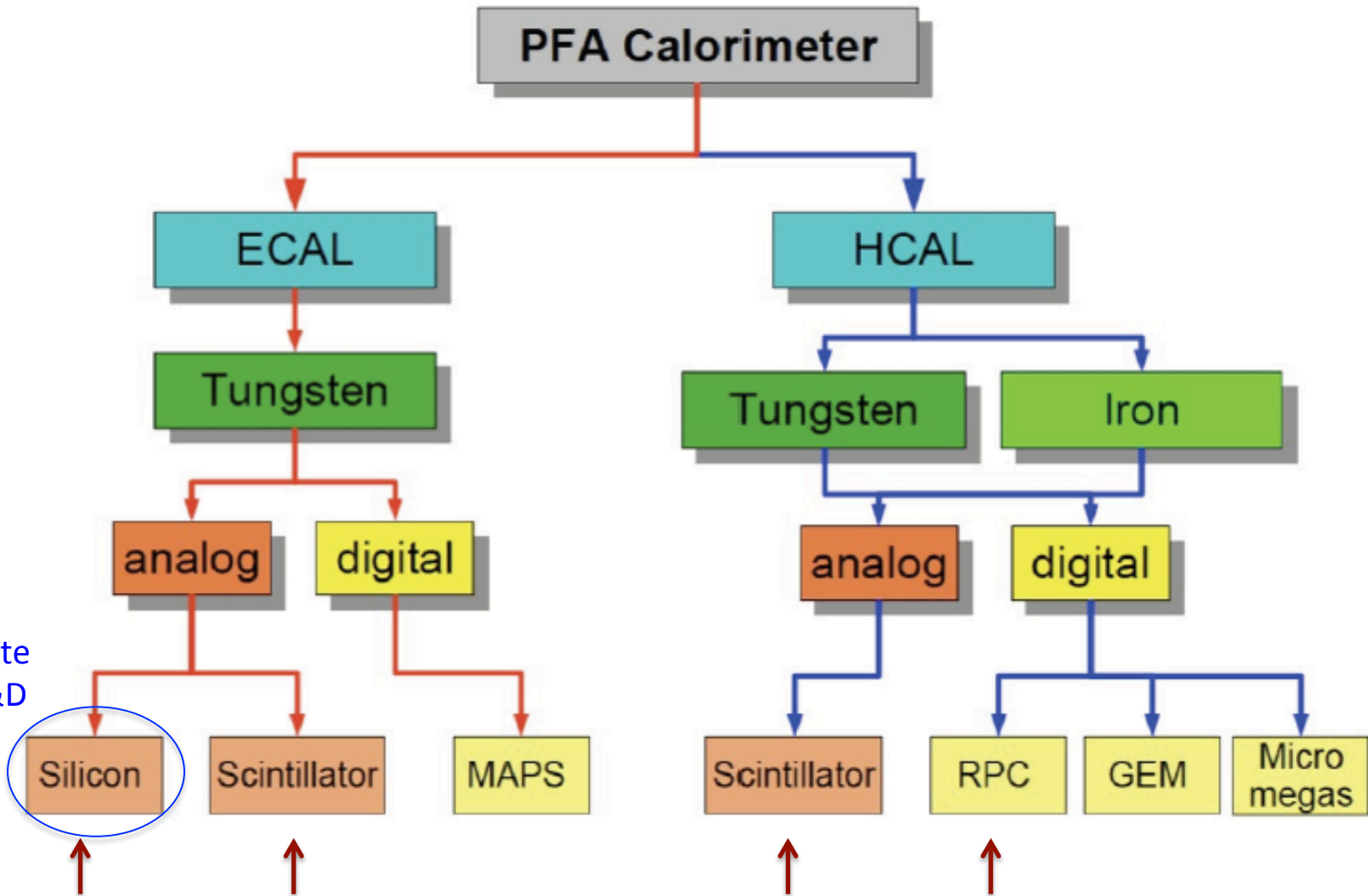
Strip: length 20 mm
width 20 μm
Pitches: implant 80 μm
readout 80 μm
Electrode: 12.2 $\Omega/\mu\text{m}$ (2.8 $\Omega/\mu\text{m}$)



$$\text{Fractional Position} \equiv y/L = S_2 / (S_1 + S_2)$$



also
separate
SiD R&D



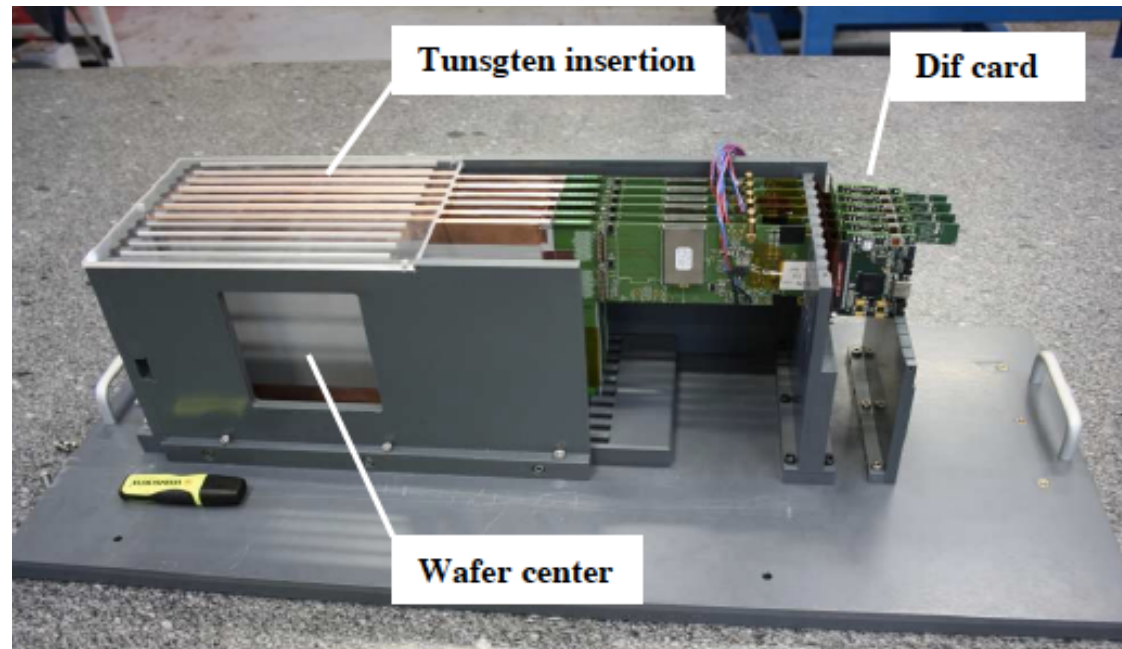
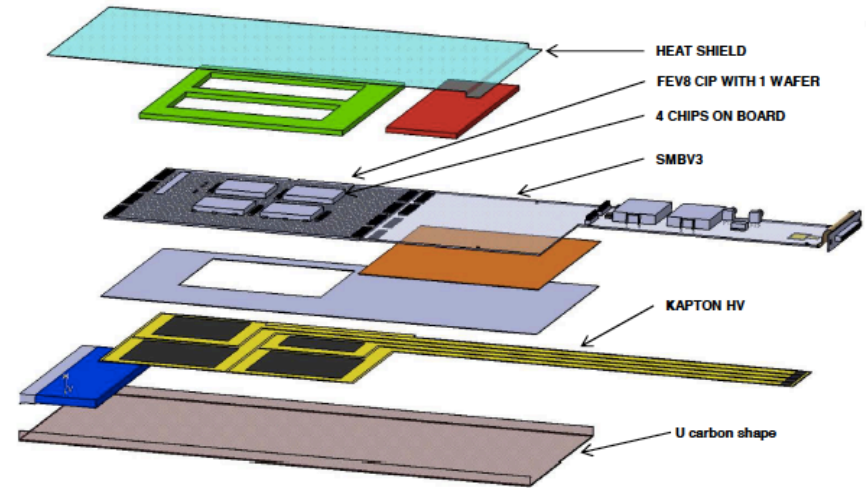
With major technological prototypes in beam tests in 2011-2012

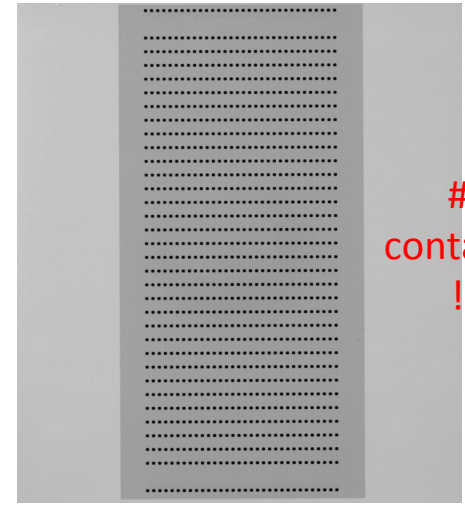
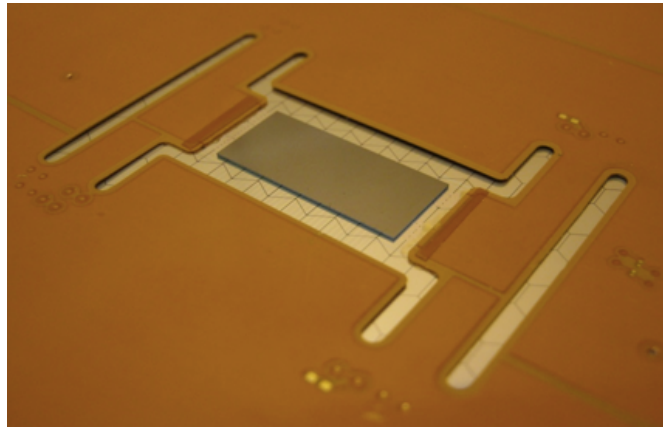
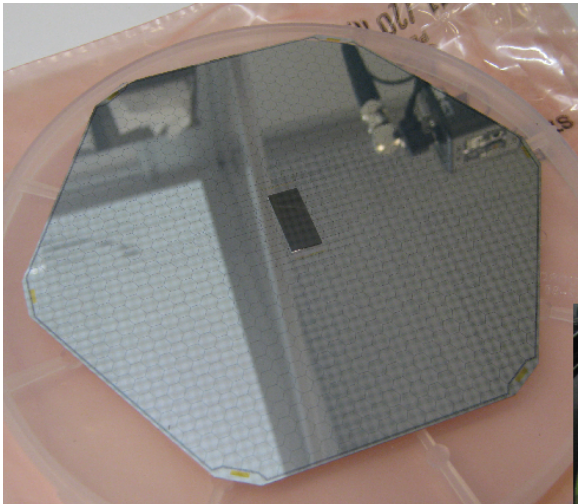
Technological Si-ECAL prototype

Real-scale detector integration model

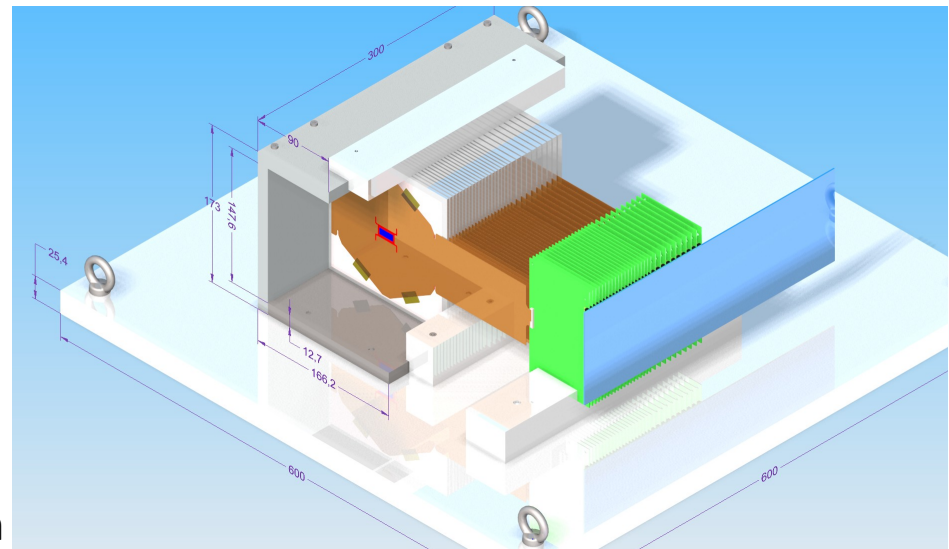
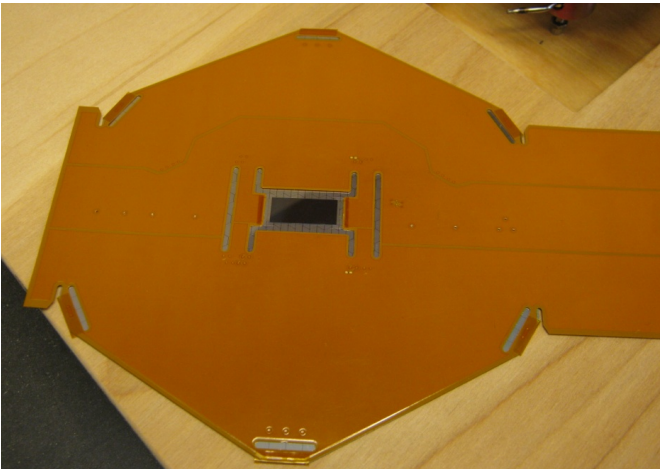
Large Si sensors with small $5 \times 5 \text{ mm}^2$ PADs
 SKIROC ASIC "in" thin PCB

System with 1200 cells in DESY test beam in 2012

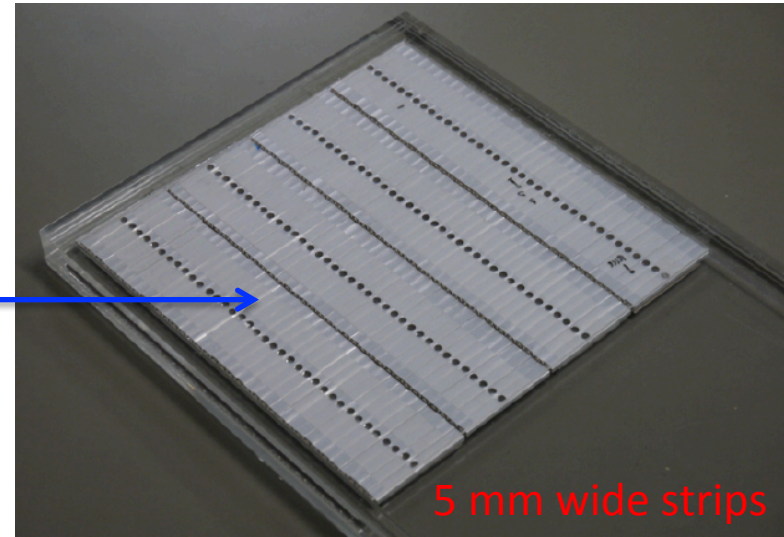
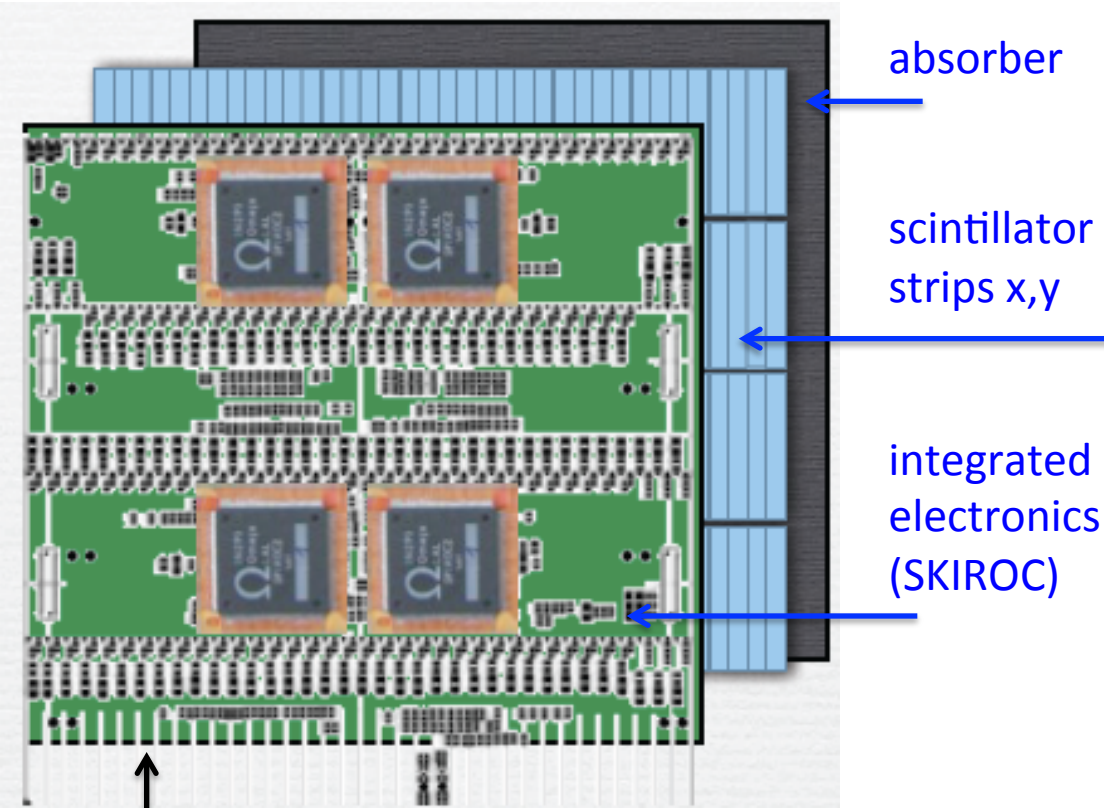




Successful **bonding** of 1024-channel KPIX chip and flex cable to SiD Silicon ECAL sensor



Test beam stack in preparation



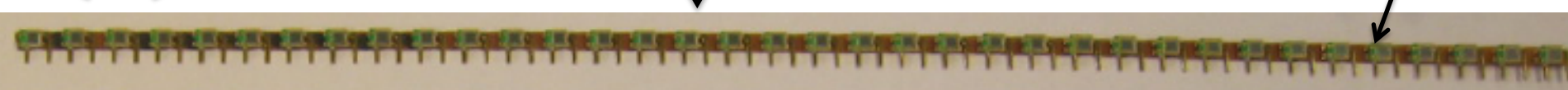
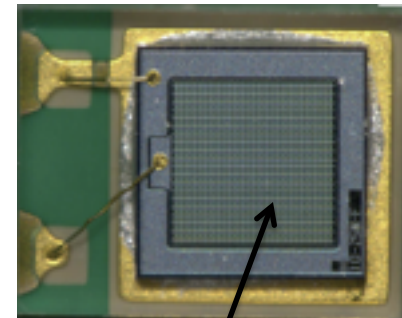
↑ Strips of $45 \times 5 \times 2 \text{ mm}^3$, 144 channels/ plane

Currently in DESY test beam, October 2012

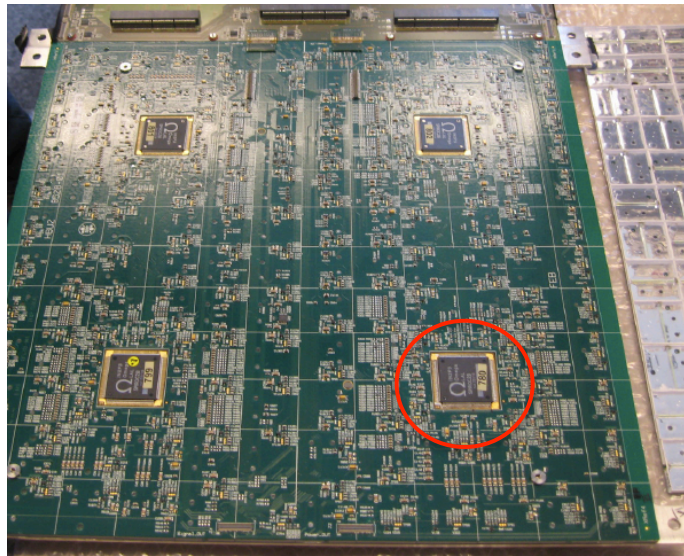
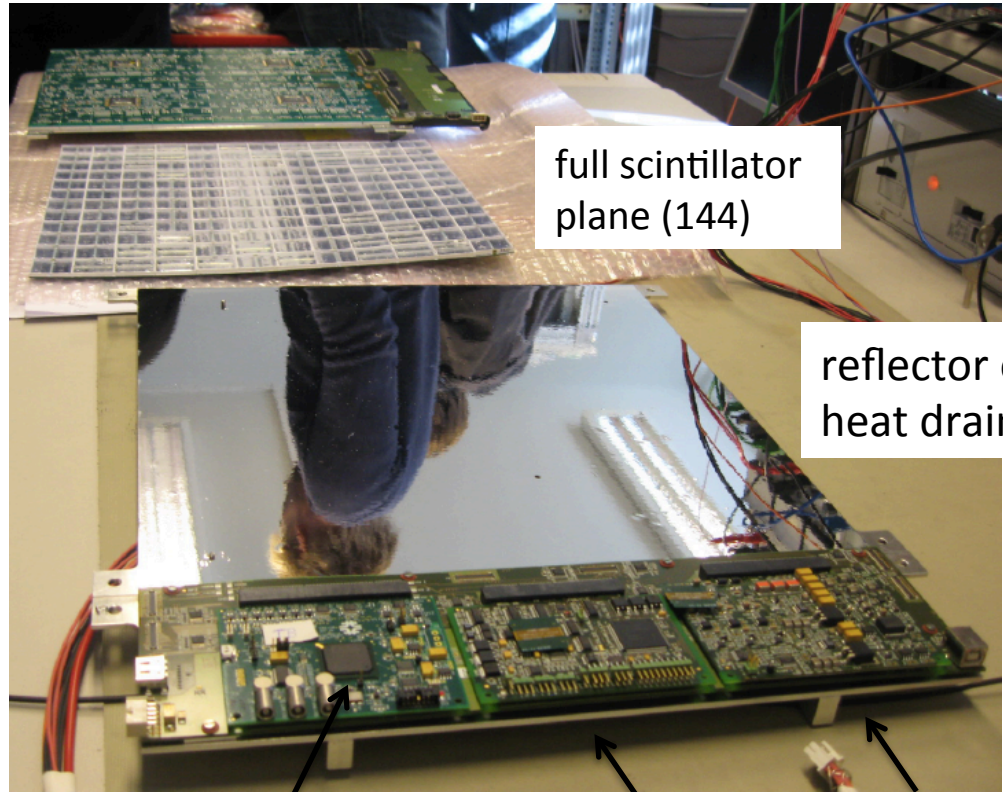
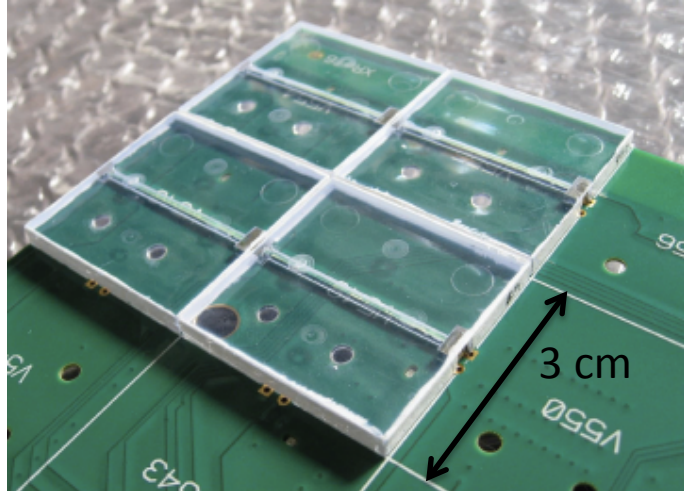
1 cm

↓ Row of MPPC (SiPM)

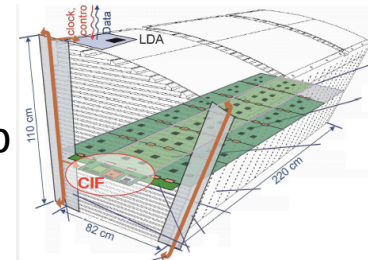
MPPC
1600 pixels
 $1 \times 1 \text{ mm}^2$

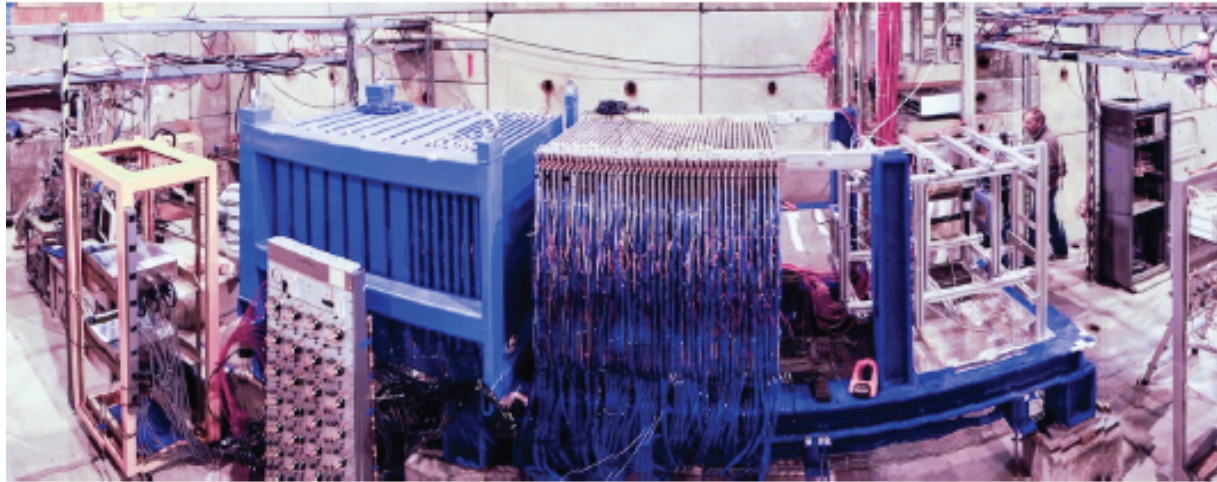


AHCAL 2nd generation fully integrated prototype planes, now in DESY test beam

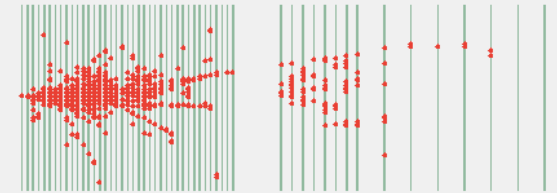


integrated electronics, based on SPIROC2b with self-triggering, timing, power pulsing

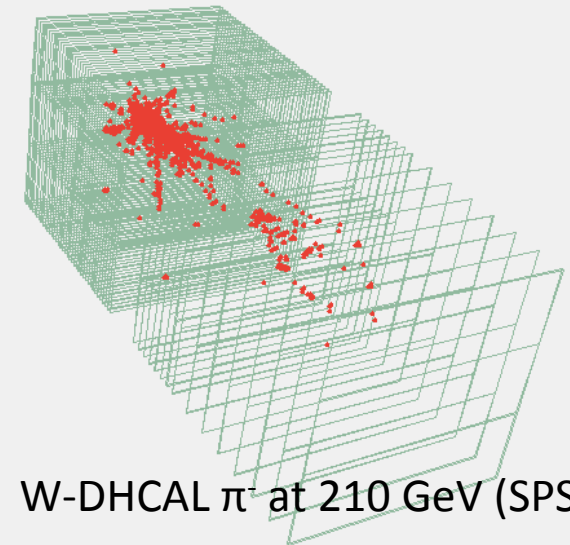
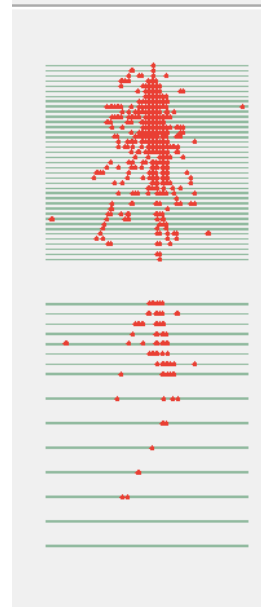




Steel DHCAL
Tungsten DHCAL
500'000 readout channels



54 glass RPC chambers, 1m² each
 PAD size 1x1 cm²
 Digital readout (1 threshold)
 100 ns time-slicing
 Fully integrated electronics
 Main DHCAL stack (39) + tail catcher (15)
 Total 500'000 readout channels



W-DHCAL π^- at 210 GeV (SPS)

Successfully tested:
 2010+2011 **Fermilab**
 Steel absorber
 2012 **CERN** PS + SPS
 Tungsten absorber

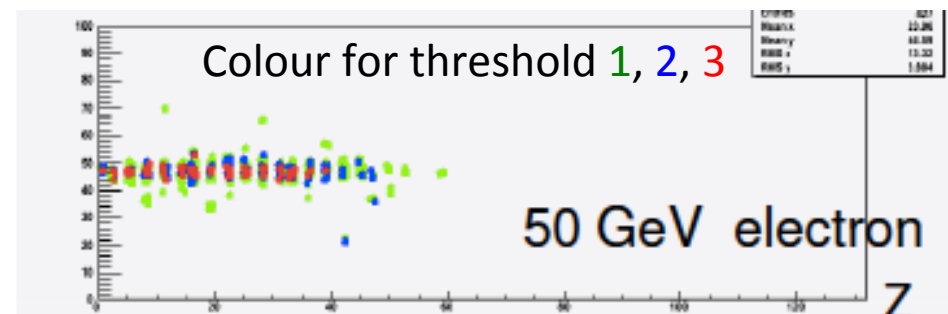
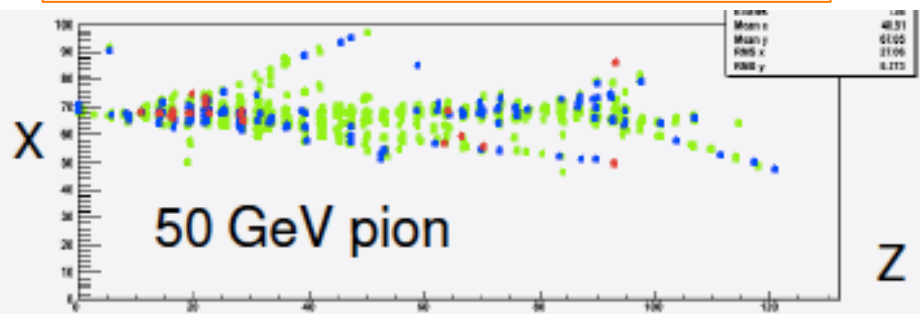
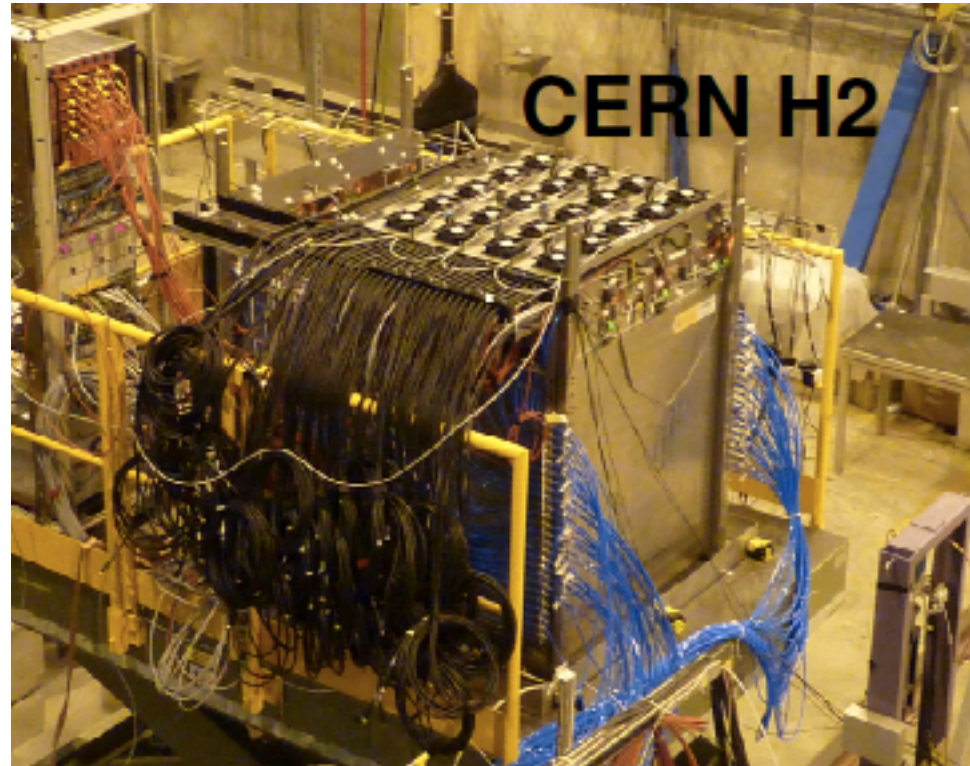
CERN test setup includes fast readout RPC after (T3B)

Steel SDHCAL
500'000 readout channels

~50 glass **RPC chambers**, 1m² each
 PAD size 1×1 cm²
 Semi-digital readout (3 thresholds)
 200 ns time-slicing
 Fully integrated electronics

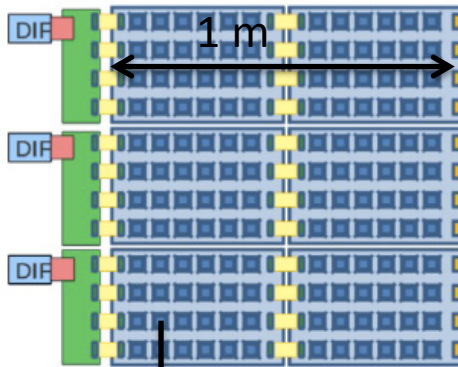
With power-pulsing !
 Separate power-pulsing tests in 3T magnet
 => Stable signal response

Full SDHCAL stack **successfully tested:**
 2012 (2011) CERN - ongoing
Steel absorber

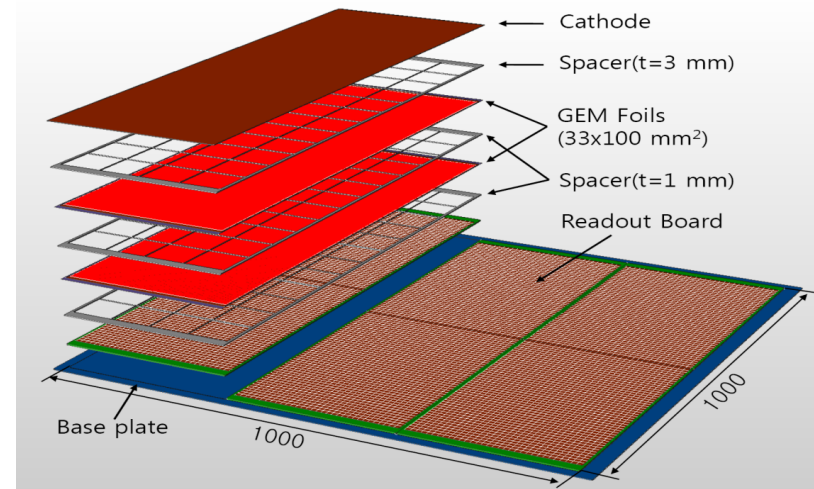
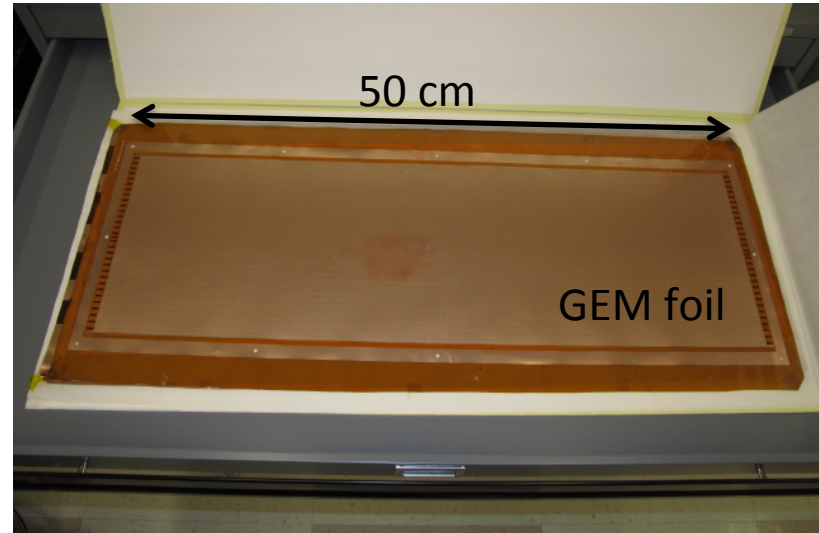
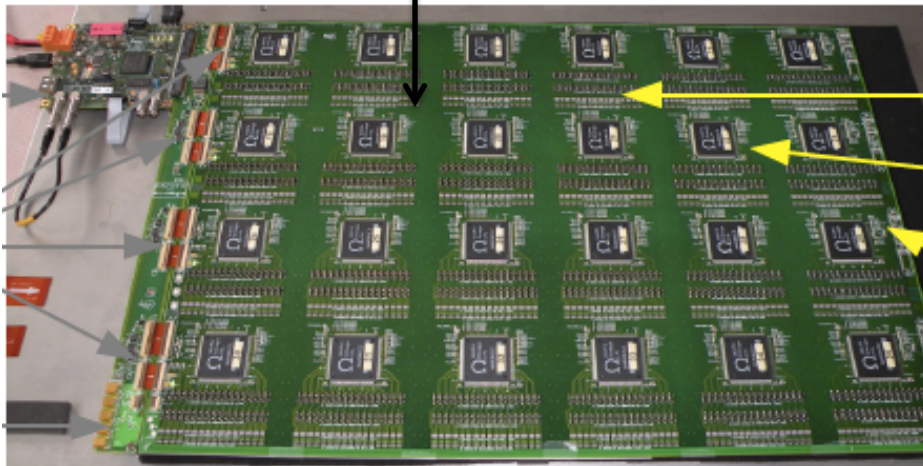


Micromegas

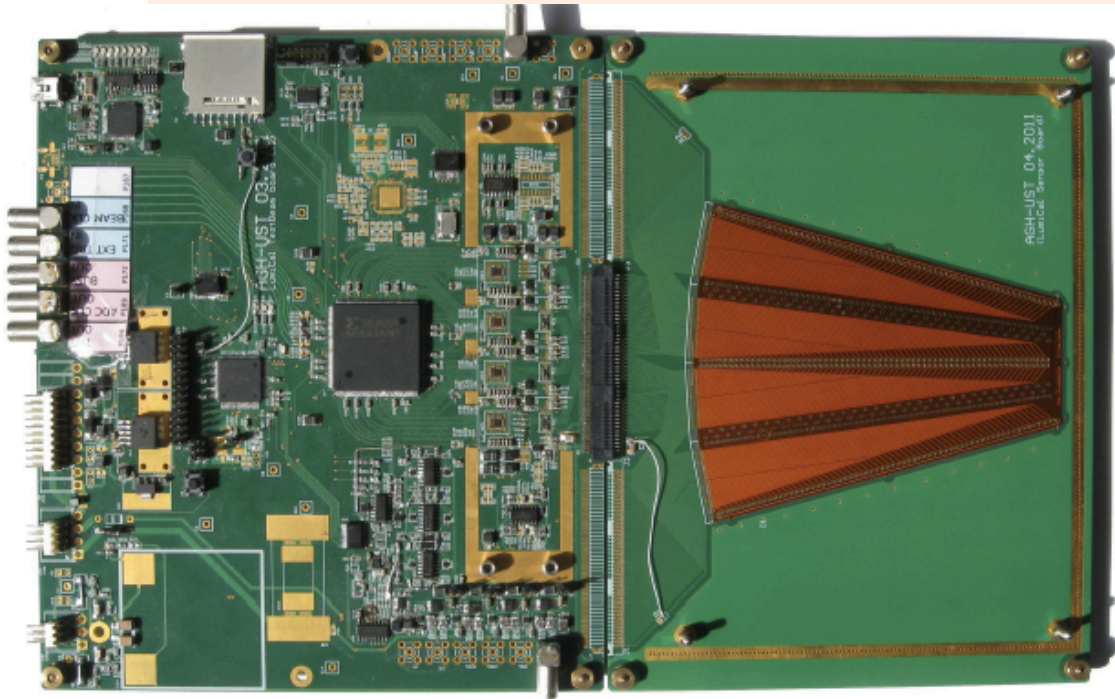
Two 1 m² chambers, multi-threshold readout
Successfully tested within SDHCAL stack, 2012



32x48 pads of 1 cm² on back side



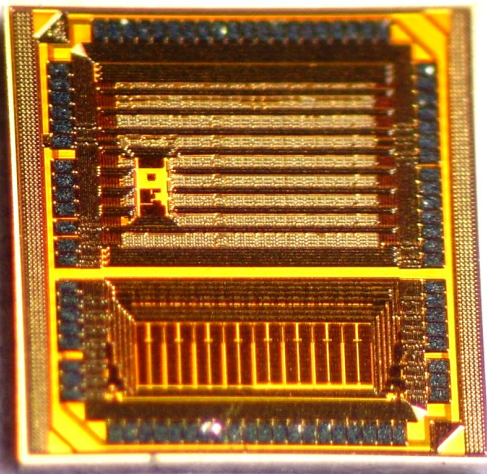
After successful tests with 30×30 cm
GEM chambers, development
 towards of 1m² plane has started.



Fully instrumented sensor planes

- Silicon (and GaAs) planes
- Dedicated FE and ADC ASICs (4-metal 350 nm CMOS techn.)
- Stable operation in beam
- S/N = 20 for MIP
- Good signal uniformity

Also: successful **radiation tests** of large-scale GaAs sensors

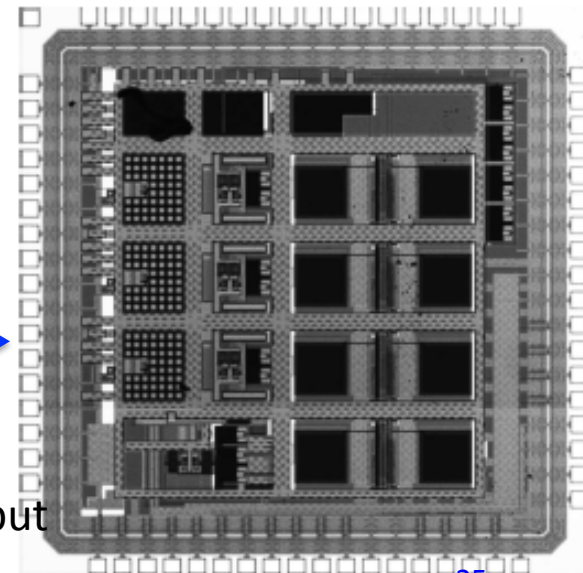


New ADC ASIC prototype 130 nm

- 8-channel, 10 bit SAR
- Fully differential
- 40 MHz

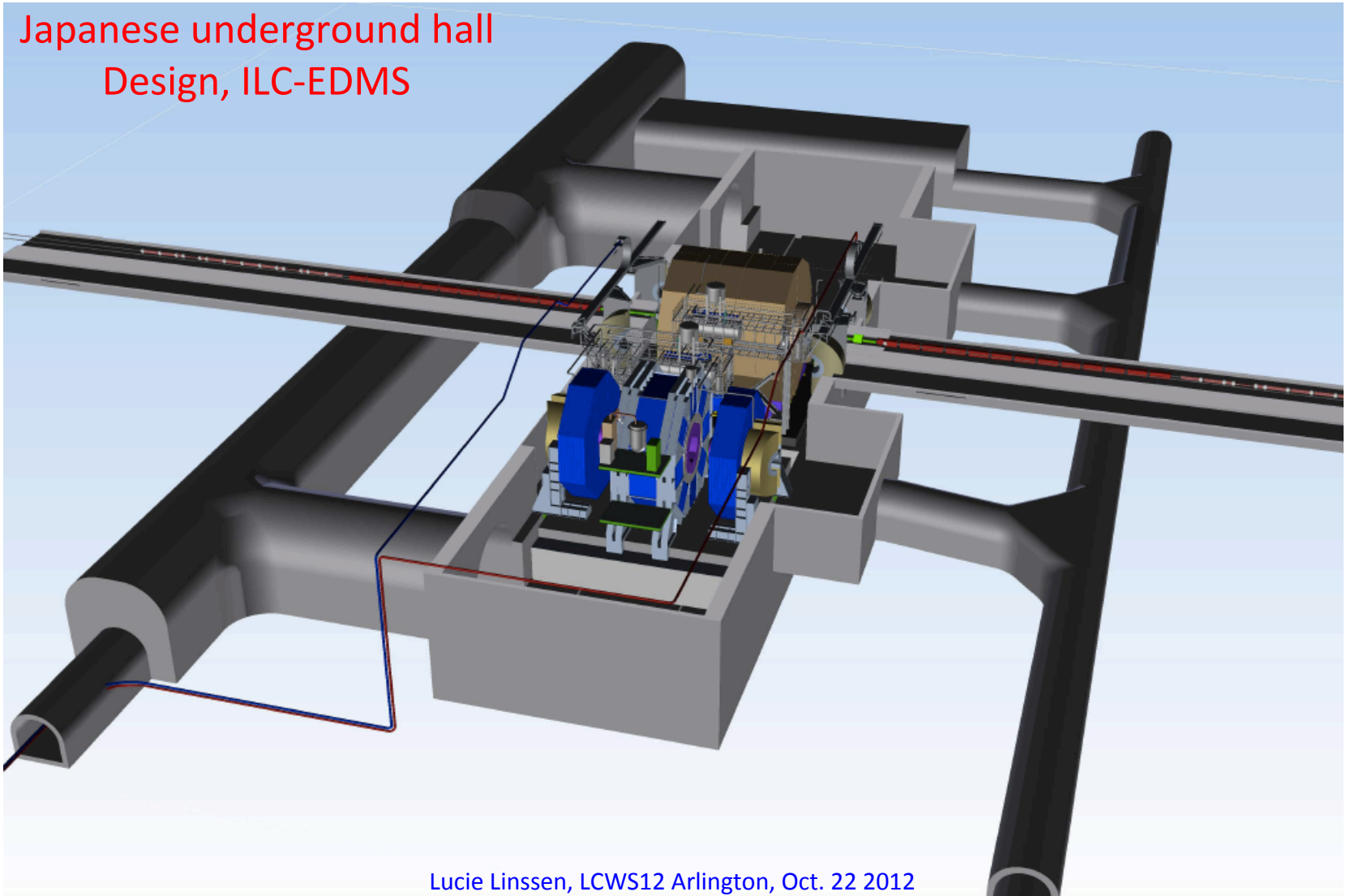
BEAN chip

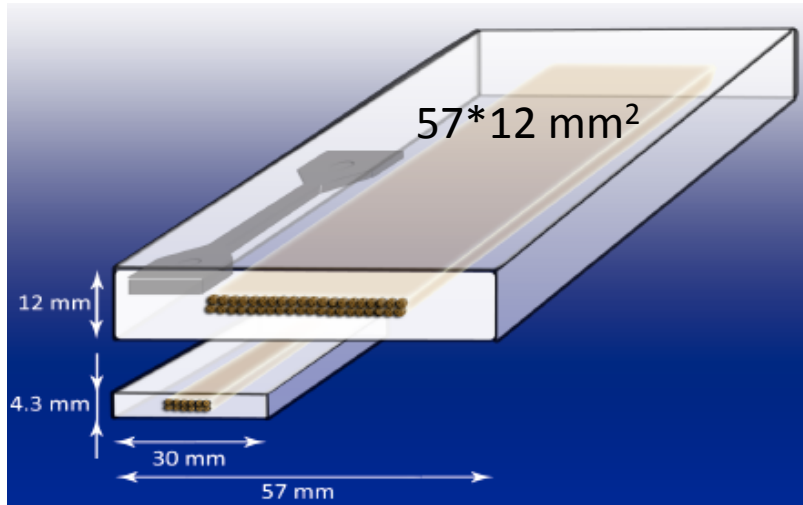
- 180 nm CMOS
- FE+ADC
- beam diagnostics output



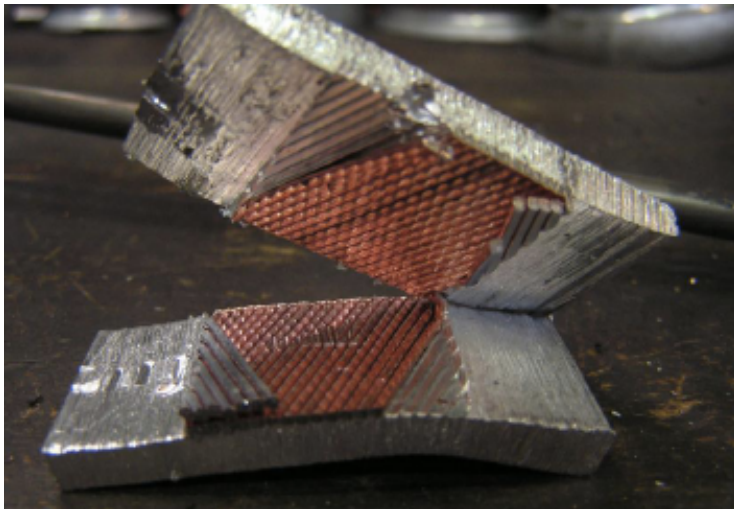
Progress in engineering work, applied from the very large to the very small
 Picture illustrates: **interplay and data exchange between ILD / SiD / accelerator**

Japanese underground hall
 Design, ILC-EDMS



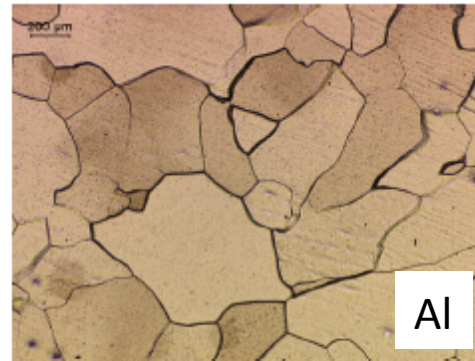


Conductor size, compared to ATLAS solenoid conductor

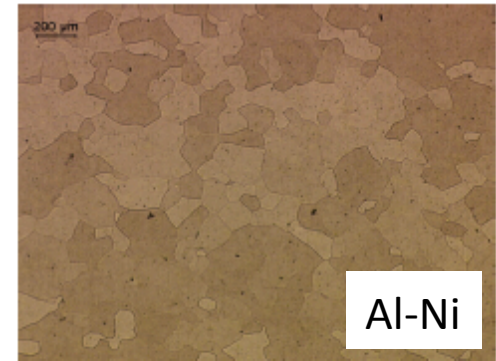


Shear test

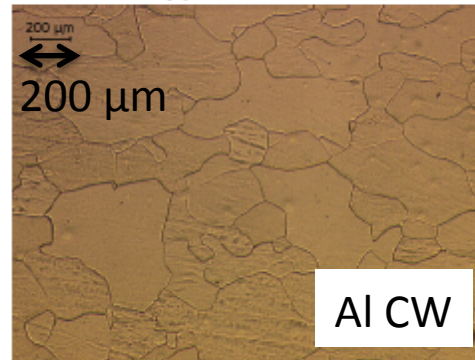
Extrusion of Al-Ni reinforced conductor



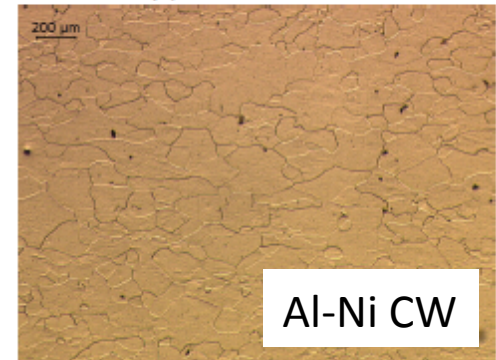
(a) Al 0% CW



(b) Al-Ni 0% CW



(c) Al 20% CW



(d) Al-Ni 20% CW

Change in material properties of Al and Al-Ni before and after cold-working

Material property trends behave as expected

Summary

Despite funding difficulties, there is a broad ongoing detector R&D program in

- Pixel detector
- TPC tracker
- Forward-region tracking
- PFA-based calorimetry + forward calorimetry
- While main silicon tracker R&D (equally challenging !) lags a bit behind

R&D is successfully moving to fully integrated technologies

- This holds in particular for calorimetry

My personal comment:

In the coming years, strengthening is required in domains of:

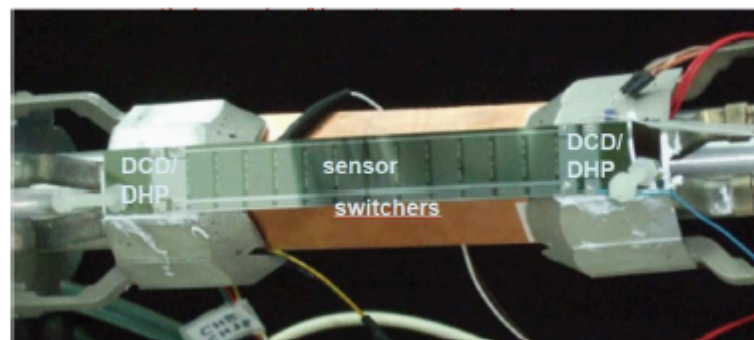
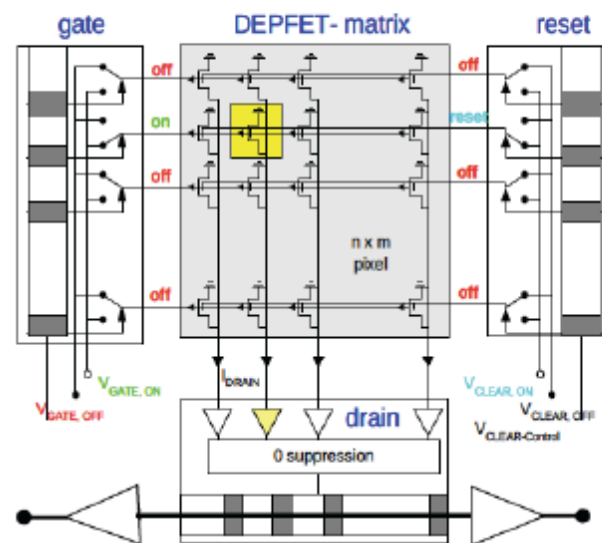
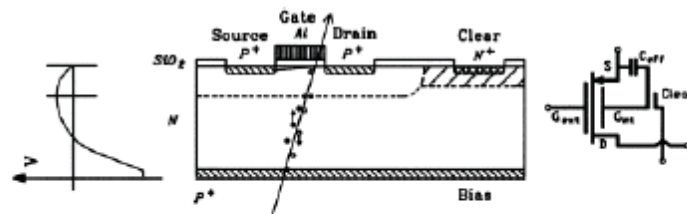
- Low-mass Vertex-detector + Tracking integration issues
- Power pulsing !

With many **thanks to:** Karsten Buesser, Dominik Dannheim, Cristian Fuentes, Wolfgang Lohmann, Jochen Kaminski, Stefanie Langeslag, Felix Sefkow, Yasuhiro Sugimoto, Tohru Takeshita, Ivan Vila

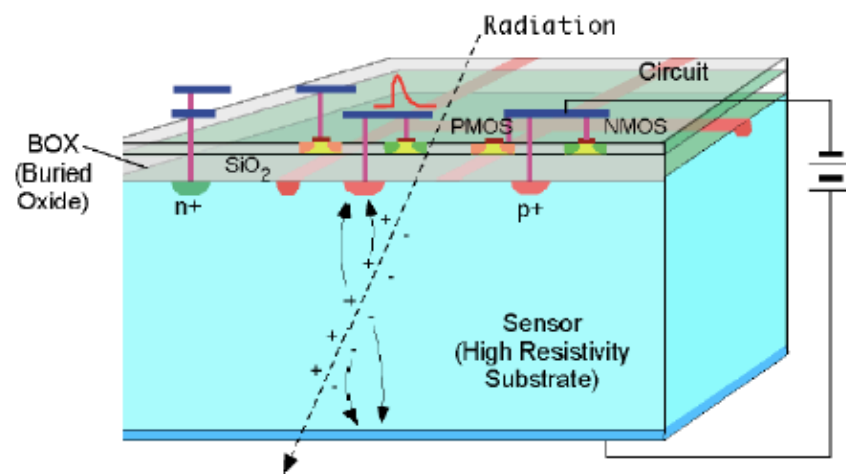
....and for DBD's and lots of material I simply found on various LC sites

SPARE SLIDES

- The Depleted Field-Effect transistor relies on a depleted layer located under a FET.
- A Potential minimum is created in the channel of the transistor
- Accumulation of charge from ionizing particles modifies charge distribution in the channel and increases transistor current
- Monolithic sensor allows for thin assembly (50 μm , ex: PXD6)
- Allows for small pixel size ($\sim 25 \times 25 \mu\text{m}$)
- Integrating sensor (Frame $\sim 25\text{-}100 \mu\text{s}$)
→ coarse time stamping

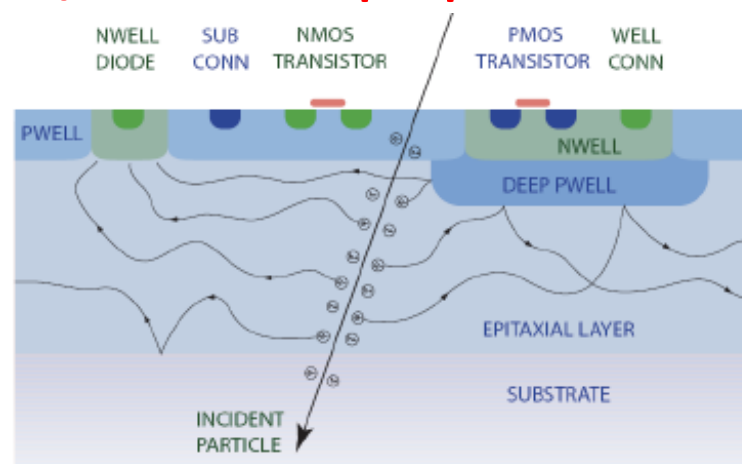


- CMOS sensor on SOI wafers
 - Fully depleted High-Resistivity sensor
 - Electronics on low resistivity wafer separated by BOX from sensing layer
- Allow for standard CMOS electronics
 - Fast time stamping possible
 - Complex pixel « intelligence »
 - Insulation of each device from bulk allows for low leakage-current operation



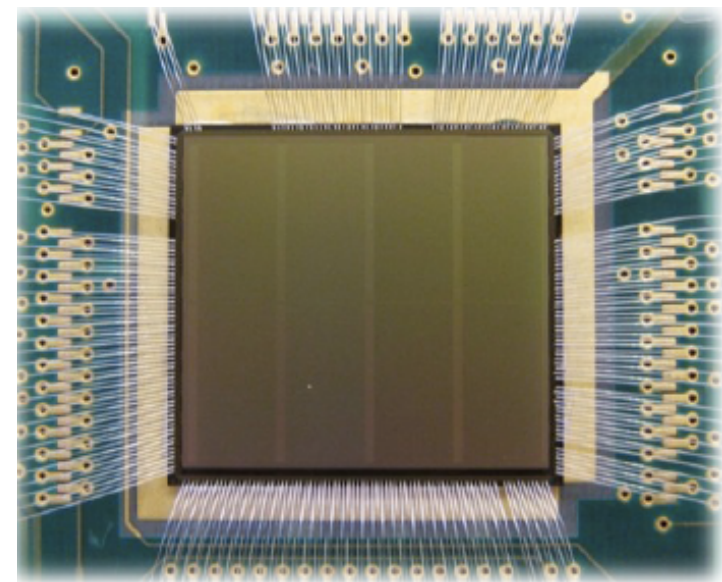
Digital ECAL concept for rates up to 100 particles/mm² => ~50 μm pixel size

- 168×168 pixel grid
- 50×50 μm² pixel size
- Digital readout
- Low noise
- INMAPS process
 - Deep P-WELL implant for charge collection
- Charge collected by diffusion to signal diodes



Successful BEAM tests at CERN and DESY

- With MIPs and particle showers
- Confirms increased MIP efficiency with INMAPS technology
- Shower multiplicity increases with incident energy => indicating validity of DECAL concept



TPAC sensor